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FlexSEM 1000 II / SU3800 / SU3900

HITACHI
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Model	Scanning Electron Microscope FlexSEM 1000 II 	Scanning Electron Microscopes SU3800 	Scanning Electron Microscopes SU3900 
Magnification	6x - 300,000x (on photo) 16x - 800,000x (on display)	5x - 300,000x (on photo) 7x - 800,000x (on display)	
Electron source	4.0 nm at 20 kV (SE, High Voltage, High Vacuum)	3.0 nm at 30 kV (SE, High Voltage, High Vacuum)	
	15.0 nm at 1 kV (SE, Low Voltage, High Vacuum)	15.0 nm at 1 kV (SE, Low Voltage, High Vacuum)	
	5.0 nm at 20 kV (BSE, High Voltage, Low Vacuum)	4.0 nm at 30 kV (BSE, High Voltage, Low Vacuum)	
Resolution	Pre-centered cartridge type tungsten hairpin filament		
Accelerating voltage	0.3 - 20 kV	0.3 - 30 kV	
Variable pressure	6 - 100 Pa	6 - 650 Pa	
Sample stage traverse	3-axis motorized stage	5-axis motorized stage	
	X : 0 - 50 mm	X : 0 - 100 mm	X : 0 - 150 mm
	Y : 0 - 40 mm	Y : 0 - 50 mm	Y : 0 - 150 mm
	Z : 5 - 33 mm	Z : 5 - 65 mm	Z : 5 - 85 mm
	T : -15 - 90°	T : -20 - 90°	
	R : 360°	R : 360°	
Maximum sample size	80 mm (in diameter) 153 mm* (in diameter)	200 mm (in diameter)	300 mm (in diameter)
Maximum sample thickness	40 mm	80 mm	130 mm
Signal detector	SE detector		
	High sensitivity semiconductor BSE detector		
	Ultra Variable-pressure Detector (UVD)*		
Analysis system	Energy Dispersive X-ray Spectrometer (EDS)*		
	Wavelength dispersive X-ray spectrometry (WDS)*		